

**IN THE SPECIFICATION**

On page 1 line 5, please insert the following:

--CROSS-REFERENCE TO RELATED APPLICATIONS

This is a Divisional Application of Application No. 09/641,125, filed on August 16, 2000. Another Divisional Application of Application No. 09/641,125, Application No. \_\_\_\_\_, was filed concurrently with this application.--

Please rewrite the paragraph on page 14, line 23, and ending on page 15, line 6, as follows:

Fig. 6 is a schematic diagram showing the selecting order of defined masks. In the method described above, assume, for example, that the defined masks MDM in the main mask MM are successively exposed from (1) to (5) and then the defined mask MDM (6) is found to be defective. Here, the corresponding defined mask in the compensation mask MM, CM, or the non-defective defined mask CDM (6), is used for the exposure. Then, returning to the main mask MM, the same exposure is performed on the next defined mask MDM (7). Subsequently, the exposure is similarly carried on by using defined masks CDM in the compensation mask CM when defined masks MDM in the main mask MM are found to be defective.